

1763



Patent
Attorney's Docket No. 015290-517

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Tuqiang NI et al.

Application No.: 09/788,365

Filed: February 21, 2001

For: GAS INJECTION SYSTEM FOR
PLASMA PROCESSING

Group Art Unit: 1763

Examiner: Unassigned

#4

**INFORMATION DISCLOSURE STATEMENT
TRANSMITTAL LETTER**

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Enclosed is an Information Disclosure Statement and accompanying form PTO-1449 for the above-identified patent application.

- ☒ [X] No additional fee for submission of an IDS is required.
- ☐ [] The fee of \$180.00 (126) as set forth in 37 C.F.R. § 1.17(p) is also enclosed.
- ☐ [] A certification under 37 C.F.R. § 1.97(e) is also enclosed.
- ☐ [] A certification under 37 C.F.R. § 1.97(e), and the fee of \$180.00 (126) as set forth in 37 C.F.R. § 1.17(p) are also enclosed.
- ☐ [] Charge \$_____ to Deposit Account No. 02-4800 for the fee due.
- ☐ [] A check in the amount of \$_____ is enclosed for the fee due.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, P.C.

By:

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Date: June 11, 2001

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INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the duty of disclosure as set forth in 37 C.F.R. § 1.56, Applicants hereby submit the following information in conformance with 37 C.F.R. §§ 1.97 and 1.98. Pursuant to 37 C.F.R. § 1.98, a copy of each of the documents cited is enclosed.

U.S. Patent No. 4,270,999, Hassan et al., issued 06/02/81;
U.S. Patent No. 4,614,639, Hegedus, issued 09/30/86;
U.S. Patent No. 4,691,662, Roppel et al., issued 09/08/87;
U.S. Patent No. 4,943,345, Asmussen et al., issued 07/24/90;
U.S. Patent No. 4,992,301, Shishiguchi et al., issued 02/12/91;
U.S. Patent No. 4,996,077, Moslehi et al., issued 02/26/91;
U.S. Patent No. 5,134,965, Tokuda et al., issued 08/04/92;
U.S. Patent No. 5,164,040, Eres et al., issued 11/17/92;
U.S. Patent No. 5,252,133, Miyazaki et al., issued 10/12/93;
U.S. Patent No. 5,522,934, Suzuki et al., issued 06/04/96;
U.S. Patent No. 5,525,159, Hama et al., issued 06/11/96;
U.S. Patent No. 5,529,657, Ishii, issued 06/25/96;
U.S. Patent No. 5,531,834, Ishizuka et al., issued 07/02/96;
U.S. Patent No. 5,540,800, Qian, issued 07/30/96;

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U.S. Patent No. 5,580,385, Paranjpe et al., issued 12/03/96

U.S. Patent No. 5,614,055, Fairbairn et al., issued 03/25/97

"Electron Cyclotron Resonance Microwave Discharges for Etching and Thin-film Deposition," J. Vacuum Science and Technology A, Vol. 7, pp. 883-893 (1989) by J. Asmussen;

"Low-temperature Deposition of Silicon Dioxide Films from Electron Cyclotron Resonant Microwave Plasmas," J. Applied Physics, Vol. 65, pp. 2457-2463 (1989) by T.V. Herak et al.;

"New Approach to Low Temperature Deposition of High-quality Thin Films by Electron Cyclotron Resonance Microwave Plasmas," J. Vac. Sci. Tech, B, Vol. 10, pp. 2170-2178 (1992) by T.T. Chau et al.;

The documents are being submitted within 3 months of the filing or entry of the national stage of this application or before the first Office Action on the merits, whichever is later, therefore no fee or certification is required under 37 C.F.R. § 1.97(b).

To assist the Examiner, the documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initialed copy of this form be returned to the undersigned:

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

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